

1 contact hole;

2 a counter electrode formed on said second substrate; and

3 a liquid crystal layer between said first and second substrate being driven by an
4 electric field between said pixel electrode and said counter electrode to thereby make a
5 display,

6 wherein said color filter is formed directly on said first substrate in most of a light
7 transmission region within a pixel area surrounded by said scanning lines and said signal
8 lines, and *a stack of layers, COMPS*

9 ~~a stacking layer of said passivation film and said color filter is formed near said~~
10 ~~contact hole, and~~ *112.2*

11 said overcoat layer is formed on said filter, and

12 said pixel electrode is formed on said color filter.

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2. (Twice Amended) An active matrix liquid crystal display device comprising:

2
3 a first substrate and a second substrate, at least one of said first and second substrate
4 being transparent;

3
5 a plurality of scanning lines formed on said first substrate;

4
6 a plurality of signal lines formed on said first substrate crossing said plurality of
7 scanning lines in a matrix manner;

8 a plurality of thin film transistors formed at each of intersections of said scanning
9 lines and said signal lines;

10 a passivation film formed on said thin film transistors;

11 at least one color filter formed on said first substrate;

12 an overcoat layer formed on said color filter;

13 a plurality of pixel electrodes connected to each of said thin film transistors through a
14 contact hole;

15 a counter electrode formed on said second substrate; and

16 a liquid crystal layer between said first and second substrate being driven by an
17 electric field between said pixel electrode and said counter electrode to thereby make a
display,

18 wherein said color filter is formed directly on said first substrate in most of a light
19 transmission region within a pixel area surrounded by said scanning lines and said signal
20 lines, and

21 a stacking layer of said passivation film, said color filter and said overcoat layer is
22 formed near said contact hole, and

23 said pixel electrode is formed on said overcoat layer.

1 6. (Twice Amended) A method of manufacturing an active matrix liquid crystal display
2 device, the method comprising:

3 forming a plurality of scanning lines on a first substrate;

4 forming a plurality of signal lines crossing the plurality of scanning lines in a matrix
5 manner;

6 forming a plurality of thin film transistors at intersections of the plurality of scanning
7 lines and the plurality of signal lines, respectively;

8 forming a pixel electrode connected to said thin film transistors;

9 forming a counter electrode on a second substrate;

10 injecting a liquid crystal between said first substrate and said second substrate and
11 sealing the liquid crystals,

12 wherein said method further comprises:

13 forming a passivation film to protect each of said thin film transistors;

14 removing part of a gate insulating layer and said passivation film of each of
15 said thin film transistors in a region surrounded by said signal lines and said scanning
16 lines;

17 forming a color filter comprising a photosensitive color resist;

18 forming a contact hole in said color filter and said passivation film on each of
19 said thin film transistors; and

20 forming a plurality of pixel electrodes comprising a transparent conductive
21 film electrically connected through said contact hole.

1 7. (Twice Amended) A method of manufacturing an active matrix liquid crystal display

2 device, the method comprising :

3 forming a plurality of scanning lines on a first substrate;

4 forming a plurality of signal lines crossing the plurality of scanning lines in a matrix
5 manner;

6 forming a plurality of thin film transistors at intersections of the plurality of scanning
7 lines and the plurality of signal lines, respectively;

8 forming a pixel electrode connected to said thin film transistors;

9 forming a counter electrode on a second substrate;

10 injecting liquid crystal between said first substrate and said second substrate and
11 sealing the liquid crystals,

12 wherein said method further comprises:

13 forming a passivation film to protect each of said thin film transistors;

14 removing part of a gate insulating layer and said passivation film of each of
15 said thin film transistors in a region surrounded by said signal lines and said scanning
16 lines;

17 forming a color filter comprising a photosensitive color resist;

18 forming an overcoat layer on said color filter;

19 patterning said overcoat layer;

20 forming a contact hole by patterning said color filter while using said overcoat
21 layer as a mask; and

22 forming a plurality of pixel electrodes comprising a transparent conductive
23 film electrically connected through said contact hole.